ABSTRACT

Disclosed are a substrate cleaning device and a substrate cleaning method, relating to the technical field of semiconductor equipment. A substrate cleaning device comprises: a cleaning unit, including a rotating carrier and a cleaning nozzle, the rotating carrier being used for carrying a substrate and driving the substrate to rotate, and the cleaning nozzle being used for spraying a cleaning liquid onto the substrate to clean the substrate; a liquid sampling unit, configured to obtain the cleaning liquid on the substrate in real time during the substrate cleaning process; a detection unit, used for receiving the cleaning liquid obtained by the liquid sampling unit and detecting the cleanliness of the cleaning liquid; a control unit, communicatively connected to the detection unit, used for controlling the cleaning parameter according to the cleanliness of the cleaning liquid. The present invention can detect the level of contamination of the current substrate more accurately, and perform smart cleaning for substrates with different levels of contamination, ensuring the cleaning quality of the substrates while also reducing the waste of cleaning liquid.